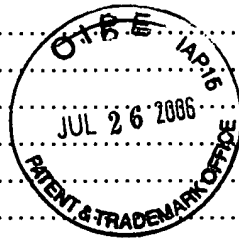


IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. .... 10/655,699  
Filing Date ..... September 5, 2003  
Confirmation No. .... 7169  
Inventor ..... Garo J. Derderian et al.  
Assignee ..... Micron Technology, Inc.  
Group Art Unit ..... 2818  
Examiner ..... Dung Anh Le  
Attorney's Docket No. .... MI22-2307  
Customer No. .... 021567  
Title: Method of Depositing a Silicon Dioxide-Comprising Layer in the  
Fabrication of Integrated Circuitry



**RESPONSE AFTER JUNE 20, 2006 NOTICE OF ALLOWANCE**  
**PRELIMINARY AMENDMENT TO ACCOMPANY RCE FILING**

To: Mail Stop RCE  
Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

**VIA EXPRESS MAIL**

From: Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)  
Wells St. John P.S.  
601 West First Avenue, Suite 1300  
Spokane, WA 99201-3828

Responsive to the Notice of Allowance dated June 20, 2006, Applicant  
amends and remarks as follows:

**AMENDMENTS**